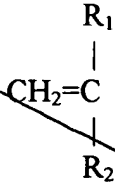


Sub 17

A1 Cont



wherein R₁ is H, or a C₁₋₃₀ straight or branched chain alkyl, aryl, or aralkyl; and R₂ is COOM wherein M is H; (CHR₁)_nOH; (CH₂CH₂O)_nH, (CH₂)_nNR₁; (CHR₁CONR₁H) where n is 1-100, and wherein the polar monomer is present at about 2 to 29% by weight of the total polymer.

Sub 17

A2

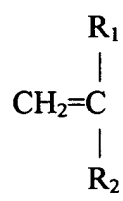
17. (Amended) A two container kit for polishing nails comprising:

(a) a first container containing a nail enamel composition comprising, by weight of the total composition:

10-95% solvent, and

5-95% of a film forming polymer having a glass transition temperature in the range of 5 to 90° C. obtained by polymerizing two different types of monomers wherein one monomer is a nonpolar ethylenically unsaturated monomer and the other monomer is a polar monomer of the

formula:



wherein R₁ is H, or a C₁₋₃₀ straight or branched chain alkyl, aryl, or aralkyl; and R₂ is COOM wherein M is H; (CHR₁)_nOH; (CH₂CH₂O)_nH, (CH₂)_nNR₁; (CHR₁CONR₁H) where n is 1-100, and wherein the polar monomer is present at about 2 to 29% by weight of the total polymer; and

Sub
P2
Cont.

(b) a second container containing a nail enamel topcoat composition comprising, by weight of the total topcoat composition:

A2
Cont

1-99% solvent, and

1-99% of a film forming polymer.

19. (Amended) A method for polishing the nails comprising:

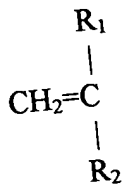
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B3

(a) applying to the nails a first composition comprising, by weight of the total composition:

10-95% solvent, and

5-95% of a film forming polymer having a glass transition temperature in the range of 5 to 90° C. obtained by polymerizing two different types of monomers wherein one monomer is a nonpolar ethylenically unsaturated monomer and the other monomer is a polar monomer of the

formula:



wherein R_1 is H, or a C_{1-30} straight or branched chain alkyl, aryl, or aralkyl; and R_2 is COOM

wherein M is H; $(CHR_1)_nOH$; $(CH_2CH_2O)_nH$; $(CH_2)_nNR_1$; (CHR_1CONR_1H) where n is 1-100,

and wherein the polar monomer is present at about 2 to 29% by weight of the total polymer; and

(b) applying to the nails a second composition comprising, by weight of the total composition:

1-99% solvent, and

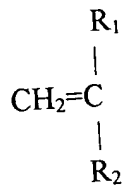
1-99% of an film forming polymer; wherein the dried film formed by (a) and (b) resides on

the nails for five to ten days.

20. Cancel.

PLEASE ADD THE FOLLOWING NEW CLAIMS:

21. The composition of claim 1 wherein the ethylenically unsaturated nonpolar monomer is a monofunctional monomer having the formula:



wherein R_1 is H, a C_{1-30} straight or branched chain alkyl, aryl, aralkyl; R_2 is H, CH_3 , a pyrrolidone, or a substituted or unsubstituted aromatic, alicyclic, or bicyclic ring where the substituents are C_{1-30} straight or branched chain alkyl, or COOM wherein M is a C_{1-30} straight or branched chain alkyl, pyrrolidone, or a substituted or unsubstituted aromatic, alicyclic, or bicyclic ring where the substituents are C_{1-30} straight or branched chain alkyl which may be substituted with one or more halogens.

22. The composition of claim 22 wherein R_1 in the nonpolar monomer is H or a C_{1-30} straight or branched chain alkyl, and R_2 in the nonpolar monomer is COOM wherein M is a C_{1-30} straight or branched chain alkyl.

23. The composition of claim 22 wherein R_1 in the nonpolar monomer is H or methyl and R_2 in the nonpolar monomer is COOM wherein M is a C_{1-4} alkyl.

24. The composition of claim 22 wherein R_1 is methyl and R_2 is COOM wherein M is butyl and the monomer is butyl methacrylate.

25. The composition of claim 24 wherein the polar monomer R_1 is H or methyl, and R_2 is COOM wherein M is H.